L Number	Hits		DB	Time stamp
1	5	(("6319821") or ("5710061") or ("6316167")	USPAT;	2003/06/05 13:53
4	56707	or ("6153504") or ("20010045646")).PN. aspect adj ratio	US-PGPUB USPAT;	-2003/06/05 -13:54
. *	- 20,70,-		US-PGPUB;	2000,00,00 20101
			EPO; JPO;	
			DERWENT	0000/05/05 10 56
10	3	((("6319821") or ("5710061") or ("6316167") or ("6153504") or	USPAT; US-PGPUB;	2003/06/05 13:56
		("20010045646")).PN.) and (aspect adj	EPO; JPO;	
		ratio)	DERWENT	
16	2	, , ,	USPAT;	2003/06/05 14:00
		("6316167") or ("6153504") or	US-PGPUB;	
		("20010045646")).PN.) and cure\$3	EPO; JPO; DERWENT	
22	16062	(aspect adj ratio) with (width height	USPAT;	2003/06/05 14:01
		size)	US-PGPUB;	
	,		EPO; JPO;	
28	3279	(aspect adj ratio) with (width with	DERWENT USPAT;	2003/06/05 14:01
20	3219	height)	US-PGPUB;	2003/00/03 14.01
			EPO; JPO;	
			DERWENT	
34	2428	(aspect adj ratio) with (width with height)	USPAT	2003/06/05 14:02
35	1563	(aspect adj ratio) near3 (width near3	USPAT	2003/06/05 14:02
		height))
36	20		USPAT	2003/06/05 14:15
37	2	height) near3 (thickness) ("6093973").PN.	USPAT;	2003/06/05 14:15
3,	2	(0033373).IN.	US-PGPUB;	2003/00/03 14.13
	i		EPO; JPO;	
4.0	200052		DERWENT	0000/05/05 14 17
43	398263	resist photoresist photo-resist	USPAT; US-PGPUB;	2003/06/05 14:17
			EPO; JPO;	
			DERWENT	
49	7184	1	USPAT;	2003/06/05 17:16
		ultra-violet ultra adj violet))	US-PGPUB; EPO; JPO;	
			DERWENT	
55	1948	(resist photoresist photo-resist) near3	USPAT;	2003/06/05 14:18
		(duv! (deep adj2 (uv ultraviolet	US-PGPUB;	
·		ultra-violet ultra adj violet)))	EPO; JPO; DERWENT	
61	9	((resist photoresist photo-resist) near3	USPAT;	2003/06/05 14:25
		(duv! (deep adj2 (uv ultraviolet	US-PGPUB;	
		ultra-violet ultra adj violet)))) with	EPO; JPO;	
		(expos\$5 irradiat\$3) with (time second minute) with (known conventional\$3	DERWENT	
		typical\$3)		
85	3	((resist photoresist photo-resist) near3	USPAT;	2003/06/05 15:19
		(duv! (deep adj2 (uv ultraviolet	US-PGPUB;	
		ultra-violet ultra adj violet)))) with (expos\$5 irradiat\$3 bak\$3) with	EPO; JPO; DERWENT	
		(temperature) with (known conventional\$3	DEKWENI	
		typical\$3)		
91	495	(resist photoresist photo-resist) with	USPAT;	2003/06/05 15:23
		(duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet))) with	US-PGPUB; EPO; JPO;	
		(heat\$3 bak\$3 temperature)	DERWENT	
97	110	(resist photoresist photo-resist) with	USPAT;	2003/06/05 17:12
		(duv! (deep adj2 (uv ultraviolet	US-PGPUB;	
		ultra-violet ultra adj violet))) with (heat\$3 bak\$3 temperature) with (cur\$3	EPO; JPO; DERWENT	
		harden\$3 insoluble)	DEVMENT	

109	63	((resist photoresist photo-resist) near3	USPAT;	2003/06/05 16:13
		(duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)))) same	US-PGPUB; EPO; JPO;	
		(hardmask hard-mask hard-adj-mask-etchstop- etch-stop etch adj stop) same (oxide	-DERWENT -	
		dioxide "sio.sub.2" dielectric insulating		
		insulator ild! imd!)		0000/06/05 16 15
115	1165	(hardmask hard-mask hard adj mask etchstop etch-stop etch adj stop) with ((oxide	USPAT; US-PGPUB;	2003/06/05 16:15
		dioxide "sio.sub.2" dielectric insulating	EPO; JPO;	
	_	insulator ild! imd!) near2 (on over))	DERWENT	
121	5	((hardmask hard-mask hard adj mask etchstop etch-stop etch adj stop) with	USPAT; US-PGPUB;	2003/06/05 16:15
·		((oxide dioxide "sio.sub.2" dielectric	EPO; JPO;	
		insulating insulator ild! imd!) near2 (on	DERWENT	
		over))) same (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj		
		violet)))		
127	18	1 12	USPAT;	2003/06/05 17:17
		((resist photoresist photo-resist) near3 (duv! (deep adj2 (uv ultraviolet	US-PGPUB; EPO; JPO;	
		ultra-violet ultra adj violet))))	DERWENT	
133	357082	(uv ultraviolet ultra-violet ultra adj	USPAT;	2003/06/05 17:16
		violet)	US-PGPUB; EPO; JPO;	
			DERWENT	
139	160	(prebak\$3 pre-bak\$3 pre adj bak\$3) with	USPAT;	2003/06/05 17:18
		((uv ultraviolet ultra-violet ultra adj violet)) with (resist photoresist	US-PGPUB; EPO; JPO;	
		photo-resist)	DERWENT	
145	5	(P = 1 = 1 = 1 = 1 = 1 = 1 = 1 = 1 = 1 =	USPAT;	2003/06/05 17:22
		((uv ultraviolet ultra-violet ultra adj violet)) with (resist photoresist	US-PGPUB; EPO; JPO;	
		photo-resist) with heat\$3 with (light	DERWENT	
151	15	radiation) (before near3 (expos\$3 irradiat\$5)) with	USPAT;	2003/06/05 17:20
		((uv ultraviolet ultra-violet ultra adj	US-PGPUB;	2003/00/03 17:20
		violet)) with (resist photoresist	EPO; JPO;	
		photo-resist) with heat\$3 with (light radiation)	DERWENT	
163	4508	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3	USPAT;	2003/06/05 17:25
		bak\$3) near3 (blanket)	US-PGPUB; EPO; JPO;	
			DERWENT	
157	46	1 11	USPAT;	2003/06/05 17:23
		(resist photoresist photo-resist) with heat\$3 with (light radiation)	US-PGPUB; EPO; JPO;	
		induty with (right radiation)	DERWENT	
169	65	The second of th	USPAT;	2003/06/05 17:31
		bak\$3) with (blanket near2 (expos\$3 irradiat\$5)) with (resist photoresist	US-PGPUB; EPO; JPO;	
1		photo-resist)	DERWENT	
175	111	((prebak\$3 pre-bak\$3 pre adj bak\$3) with (resist photoresist photo-resist) with	USPAT; US-PGPUB;	2003/06/05 17:30
		heat\$3 with (light radiation)) ((prebak\$3	EPO; JPO;	,
		pre-bak\$3 pre adj bak\$3 heat\$3 bak\$3) with	DERWENT	
		(blanket near2 (expos\$3 irradiat\$5)) with (resist photoresist photo-resist))		
181	3	1	USPAT;	2003/06/05 17:38
		bak\$3) with (blanket near2 (expos\$3	US-PGPUB;	
		irradiat\$5)) with (resist photoresist photo-resist) with (during "same time")	EPO; JPO; DERWENT	
187	3	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3	USPAT;	2003/06/05 17:37
		bak\$3) with (flood near2 (expos\$3	US-PGPUB;	
		<pre>irradiat\$5)) with (resist photoresist photo-resist) with (during "same time")</pre>	EPO; JPO; DERWENT	
193	2543	((blanket flood) near2 (expos\$3	USPAT;	2003/06/05 17:38
		irradiat\$5))	US-PGPUB; EPO; JPO;	
			DERWENT	
		<u> </u>		L

199	406	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3	USPAT;	2003/06/05 17:41
		bak\$3) with (((blanket flood) near2	US-PGPUB;	
		(expos\$3 irradiat\$5)))	EPO; JPO;	
205	22	(prebak\$3 pre-bak\$3 pre adj bak\$3 heat\$3	DERWENT USPAT;	2003/06/05 18:14
203	22	bak\$3) with (((blanket flood) near2	US-PGPUB;	2003/00/03 10:14
		(expos\$3 irradiat\$5))) with (((uv	EPO; JPO;	
]	ultraviolet ultra-violet ultra adj violet)	DERWENT	
) (duv! (deep adj2 (uv ultraviolet	551(1151(1	
		ultra-violet ultra adj violet)))) with		
i		(resist photoresist photo-resist)		l i
211	115	etch\$4 with fluorocarbon with polymer\$3	USPAT;	2003/06/05 18:20
		with (oxide dielectric insulating	US-PGPUB	
		insulator)		1
214	0	(etch\$4 with fluorocarbon with polymer\$3	USPAT;	2003/06/05 18:17
		with (oxide dielectric insulating	US-PGPUB	
	}	insulator)) with (remov\$3) with ((duv!		
		(deep adj2 (uv ultraviolet ultra-violet		
		ultra adj violet))) ((uv ultraviolet	i	
	†	ultra-violet ultra adj violet)))		
217	13		USPAT;	2003/06/05 18:17
]	with (oxide dielectric insulating	US-PGPUB	
	_	insulator)) with (remov\$3)		0000/05/55
223	7	fluorocarbon with polymer\$3 with (reduc\$3	USPAT;	2003/06/05 18:25
		decreas\$3 less smaller) with ((duv! (deep	US-PGPUB;	
		adj2 (uv ultraviolet ultra-violet ultra	EPO; JPO;	
1	İ	adj violet))) ((uv ultraviolet	DERWENT;	
220		ultra-violet ultra adj violet)))	IBM_TDB	2003/06/05 18:27
230	50		USPAT;	2003/06/05 18:2/
		decreas\$3 less smaller) with (light	US-PGPUB; EPO; JPO;	
		radiation irradiat\$5 expos\$5)	DERWENT;	
}			IBM TDB	
237	2	fluorocarbon with polymer\$3 with (reduc\$3	USPAT;	2003/06/05 18:35
237	_	decreas\$3 less smaller) with (light	US-PGPUB;	2003/00/03 10:33
		radiation irradiat\$5 expos\$5) with etch\$3	EPO; JPO;	
		radiation relation on post of when soon to	DERWENT;	
			IBM TDB	
244	6	fluorocarbon with polymer\$3 with (reduc\$3	USPAT;	2003/06/05 18:36
		decreas\$3 less smaller) with (light	US-PGPUB;	
		radiation irradiat\$5 expos\$5) with plasma	EPO; JPO;	
	•		DERWENT;	
			IBM_TDB	
251	5		USPAT;	2003/06/05 18:39
		decreas\$3 less smaller) with (light	US-PGPUB;	
		radiation irradiat\$5 expos\$5) with	EPO; JPO;	
		deposit\$5	DERWENT;	
258	8	/fluorogorbon with malamanda with /www. 43	IBM_TDB	2002/06/05 10 42
258	8	(fluorocarbon with polymer\$3 with (reduc\$3	USPAT;	2003/06/05 18:43
		decreas\$3 less smaller) with (light radiation irradiat\$5 expos\$5) with plasma)	US-PGPUB; EPO; JPO;	
		(fluorocarbon with polymer\$3 with (reduc\$3	DERWENT;	
		decreas\$3 less smaller) with (light	IBM TDB	
		radiation irradiat\$5 expos\$5) with	1511_155	
		deposit\$5)		
265	239	(((duv! (deep adj2 (uv ultraviolet	USPAT;	2003/06/05 18:50
		ultra-violet ultra adj violet))) ((uv	US-PGPUB;	2000,00,00 20100
		ultraviolet ultra-violet ultra adj violet)	EPO; JPO;	
)) near3 cur\$3) with temperature with	DERWENT;	
		(time seconds! minute)	IBM TDB	
272	10	(((duv! (deep adj2 (uv ultraviolet	USPĀT;	2003/06/05 18:47
		ultra-violet ultra adj violet))) ((uv	US-PGPUB;	
		ultraviolet ultra-violet ultra adj violet)	EPO; JPO;	
)) near3 cur\$3) with temperature with	DERWENT;	
1		(time seconds! minute)) with (resist	IBM_TDB	
		photoresist photo-resist)	_	
279	141	(((duv! (deep adj2 (uv ultraviolet	USPAT	2003/06/05 18:51
		ultra-violet ultra adj violet))) ((uv		
		ultraviolet ultra-violet ultra adj violet)		
)) near3 cur\$3) with temperature with		
	l	(time seconds! minute)		i

280	13	((((duv! (deep adj2 (uv ultraviolet	USPAT	2003/06/05 18:51
		ultra-violet ultra adj violet))) ((uv		2000,00,00
		ultraviolet ultra-violet ultra adj violet))) near3 cur\$3) with temperature with		
		(time seconds! minute)) same (resist photoresist photo-resist)		
_	194		USPAT;	2003/06/05 11:41
		chen-tsung-chuanin. chen-t-c.in.	US-PGPUB;	
		hsu-shew-tsuin. hsu-s-tin.	EPO; JPO;	
_	4	ma-ching-tienin. chen-tsung-chuanin.	DERWENT USPAT;	2003/06/05 11:42
	•	hsu-shew-tsuin.	US-PGPUB;	
			EPO; JPO;	
	398263	resist photoresist photo-resist	DERWENT USPAT;	2003/06/05 14:17
_	390203	lesist photoresist photo-resist	US-PGPUB;	2003/00/03 14.1/
			EPO; JPO;	
	211500		DERWENT	0000/05/05 12 44
-	311522	photosensitive photo-sensitive (sensitive near (photo light energy radiation))	USPAT; US-PGPUB;	2003/06/05 11:44
		hear (photo right energy radiation)	EPO; JPO;	
			DERWENT	
-	7184		USPAT;	2003/06/05 14:17
		ultra-violet ultra adj violet))	US-PGPUB; EPO; JPO;	
			DERWENT	
-	100791	krf arf f2 "f.sub.2"	USPAT;	2003/06/05 11:47
			US-PGPUB; EPO; JPO;	
			DERWENT	
-	8980	("157" "193" "248") near (nm! nanometer	USPAT;	2003/06/05 11:48
		nano-meter nano adj meter)	US-PGPUB; EPO; JPO;	
			DERWENT	
_	242860	(oxide dioxide) near (layer film coating)	USPAT;	2003/06/05 11:50
			US-PGPUB;	
			EPO; JPO; DERWENT	
_	15996	etchstop etch-stop etch adj stop hardmask	USPAT;	2003/06/05 11:50
		hard-mask hard adj mask	US-PGPUB;	
			EPO; JPO; DERWENT	
_	1556036	si silicon si-contain\$3 silicon-contain\$3	USPAT;	2003/06/05 11:50
į.			US-PGPUB;	
			EPO; JPO; DERWENT	
_	201724	(silicon adj (nitride oxynitride	USPAT;	2003/06/05 11:58
		oxy-nitride oxy adj nitride carbide))	US-PGPUB;	
		"si.sub.3 n.sub.4" sion sic	EPO; JPO; DERWENT	
_	1179	((resist photoresist photo-resist)	USPAT;	2003/06/05 11:58
		(photosensitive photo-sensitive (sensitive	US-PGPUB;	
		near (photo light energy radiation))))	EPO; JPO;	
		near (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)))	DERWENT	
_	16		USPAT;	2003/06/05 12:06
		(photosensitive photo-sensitive (sensitive	US-PGPUB;	
		near (photo light energy radiation)))) near (duv! (deep adj2 (uv ultraviolet	EPO; JPO; DERWENT	
		ultra-violet ultra adj violet)))) same	DITTANDIA I	
		((oxide dioxide) near (layer film		
		coating)) same (etchstop etch-stop etch		
_	18	<pre>adj stop hardmask hard-mask hard adj mask) (((resist photoresist photo-resist)</pre>	USPAT;	2003/06/05 12:10
		(photosensitive photo-sensitive (sensitive	US-PGPUB;	
		near (photo light energy radiation))))	EPO; JPO;	
		near (duv! (deep adj2 (uv ultraviolet ultra-violet ultra adj violet)))) with	DERWENT .	
		cur\$3		

	10050	//waist shotorogist shoto-regist \	USPAT;	2003/06/05 12:12
-	19859	((resist photoresist photo-resist) (photosensitive photo-sensitive (sensitive	US-PGPUB;	2003/06/05 12:12
	İ	near (photo light energy radiation))))	EPO; JPO;	
		with cur\$3	DERWENT -	
<u></u> -	6163		USPAT;	2003/06/05 12:12
	0105	(photosensitive photo-sensitive (sensitive	US-PGPUB;	2003,00,03 12.12
		near (photo light energy radiation))))	EPO; JPO;	
1		with ((duv! (deep adj2 (uv ultraviolet	DERWENT	
	1	ultra-violet ultra adj violet))) (krf arf	DEIE.	•
		f2 "f.sub.2") (("157" "193" "248") near		
	1	(nm! nanometer nano-meter nano adj		
1		meter)))		
1 -	6524		USPAT;	2003/06/05 12:12
		hard-mask hard adj mask) with ((si silicon	US-PGPUB;	
		si-contain\$3 silicon-contain\$3) ((silicon	EPO; JPO;	
		adj (nitride oxynitride oxy-nitride oxy	DERWENT	
		adj nitride carbide)) "si.sub.3 n.sub.4"		
		sion sic))		
-	21	(((resist photoresist photo-resist)	USPAT;	2003/06/05 12:36
		(photosensitive photo-sensitive (sensitive	US-PGPUB;	
		near (photo light energy radiation))))	EPO; JPO;	
		with cur\$3) and (((resist photoresist	DERWENT	
		photo-resist) (photosensitive		
		photo-sensitive (sensitive near (photo		1
		light energy radiation)))) with ((duv!		
		(deep adj2 (uv ultraviolet ultra-violet		
		ultra adj violet))) (krf arf f2 "f.sub.2")		
		(("157" "193" "248") near (nm! nanometer	}	
	1	nano-meter nano adj meter)))) and	ļ	
1		((etchstop etch-stop etch adj stop		
1		hardmask hard-mask hard adj mask) with		
		((si silicon si-contain\$3		
		silicon-contain\$3) ((silicon adj (nitride		
	1	oxynitride oxy-nitride oxy adj nitride		
		carbide)) "si.sub.3 n.sub.4" sion sic)))		
1		and ((oxide dioxide) near (layer film		
	5.67.57	coating))		0000/05/05 10 05
-	56707	aspect adj ratio	USPAT;	2003/06/05 12:36
ì			US-PGPUB;	
			EPO; JPO; DERWENT	
1_	4	(((resist photoresist photo-resist)	USPAT;	2003/06/05 13:53
1 =	4	((tresist photoresist photo-resist) (photosensitive photo-sensitive (sensitive	US-PGPUB;	2003/00/03 13:53
		near (photo light energy radiation))))	EPO; JPO;	
		near (duv! (deep adj2 (uv ultraviolet	DERWENT	
		ultra-violet ultra adj violet)))) with	DEKWENT	
1		cur\$3 with (light radiation)		
	1	,, (1	1